

2018 EUVL Workshop

June 11-14, 2018

The Center for X-ray Optics (CXRO) Lawrence Berkeley National Laboratory, Berkeley, CA, USA

FIRST CALL FOR PAPERS

We are inviting presentations and poster papers for the 2018 EUVL Workshop, to be held June 11-14, 2018 at The Center for X-ray Optics (CXRO) at Lawrence Berkeley National Laboratory in Berkeley, CA. This workshop, now in its eleventh year, is focused on the fundamental science of EUV Lithography (EUVL). A smaller group setting suitable for networking and brainstorming, with a focus on fundamentals, sets this conference apart from other larger conferences based on the commercial aspects of EUVL.

Technology review papers and presentations with innovative approaches to current EUV Lithography-related technical challenges are encouraged. EUV Lithography-related topics covered under this workshop include sources for high volume manufacturing (HVM) and metrology, masks, optics, resist, contamination, metrology and patterning. Papers on combinations of EUVL with multiple patterning, extension of EUVL to 3 nm and beyond are welcome. A detailed list of topics for the 2018 EUVL workshop has been published on our website <u>www.euvlitho.com</u>.

The workshop will be preceded by an EUV Lithography Short Course on June 11. Registration for the workshop begins on June 12, followed by presentations, panel discussions and a poster session on June 13 and 14. The keynote speakers for the 2018 workshop will be announced soon on our website <u>www.euvlitho.com</u>. The 2018 EUVL Lithography is co-organized by EUV Litho, Inc. and The Center for X-ray Optics (CXRO) at Lawrence Berkeley National Laboratory, Berkeley, CA.

Instructions for Submissions and Deadlines

Please submit abstracts of less than 200 words and indicate whether an oral or poster paper is preferred. Please also include each author's full name, e-mail address, affiliation and mailing address, together with a brief biography and photograph for the presenting author. Abstracts should be submitted via email to <u>abstracts@euvlitho.com</u>. **The deadline for abstract submission is March 16, 2018.** Authors will be notified by March 23 or earlier if their abstracts have been accepted for an oral or poster paper. Travel and registration information will be available at our website by end of March 2018. For logistics related issues please contact Meeting Services at <u>info@euvlitho.com</u> and for technical questions, please contact Vivek Bakshi at <u>vivek.bakshi@euvlitho.com</u> or Patrick Naulleau at <u>pnaulleau@lbl.gov</u>.



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